

SHEET 1 OF 6

FORM PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE							ATTORNEY DOCKET NO. 1945.P3/UCA/SILICON			SERIAL NO.: N/A	
									APPLICANT: Shen, et al.				
									FILING DATE: Herewith			GROUP: Unknown	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)													
U.S. PATENT DOCUMENTS													
Examiner Initial		DOCKET NUMBER						DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
A1		4	2	8	2	2	6	7	Kavel	427	38	04/21/84	
A2		4	4	3	3	2	2	8	Nishimatsu, et al.	219	10.55 R	04/21/84	
A3		4	4	6	5	5	3	2	Fukano	156	643	04/21/84	
A4		4	4	9	0	2	0	9	Hartman	156	643	04/21/84	
A5		4	5	0	2	9	1	4	Trumbo, et al.	156	643	04/21/84	
A6		4	5	7	6	6	9	2	Fukuta, et al.	204	165	04/21/84	
A7		4	7	0	5	5	9	5	Otudaira, et al.	156	643	04/21/84	
A8		4	7	3	8	7	4	8	Kisa	156	643	04/21/84	
A9		4	7	8	6	3	5	2	Benzing	156	345	04/21/84	
A10		4	8	1	8	3	2	6	Liu, et al.	156	345	04/21/84	
A11		4	8	3	1	9	6	3	Saito, et al.	118	723	04/23/89	
A12		4	8	6	3	5	6	1	Freeman, et al.	156	646	04/23/89	
A13		4	8	6	7	8	4	1	Loewenstein, et al.	156	643	04/23/89	
A14		4	8	7	6	2	1	2	Koury	437	34	04/23/89	
A15		4	9	7	5	1	4	4	Yamazaki, et al.	156	643	04/23/89	
A16		4	9	9	2	1	3	6	Tachi, et al.	156	643	04/23/89	
A17		4	9	9	4	4	1	0	Sun, et al.	437	192	04/23/89	
A18		5	0	0	2	6	3	2	Loewenstein, et al.	156	643	04/23/89	
A19		5	0	1	3	3	9	8	Long, et al.	156	643	04/23/89	
A20		5	0	3	5	7	6	8	Mu, et al.	156	626	04/23/89	
A21		5	0	8	4	1	2	6	McKee	156	345	04/23/89	
A22		5	0	9	4	7	1	2	Becker, et al.	156	643	04/23/89	
A23		5	1	1	0	4	0	8	Fujii, et al.	156	643	05/05/92	
A24		5	1	1	0	4	1	1	Long	156	656	05/05/92	
A25		5	1	1	8	3	8	7	Kadomura	156	657	05/05/92	
A26		5	1	5	8	6	4	4	Cheung, et al.	156	643	05/05/92	
A27		5	1	6	0	4	0	7	Latchford, et al.	156	656	05/05/92	
A28		5	1	6	4	3	3	0	Davis, et al.	437	192	05/05/92	
A29		5	1	7	6	7	9	2	Fulowan, et al.	156	652	05/05/92	
A30		5	1	8	8	9	8	0	Lai	437	193	05/05/92	
EXAMINER: <i>Shen, et al.</i>										DATE CONSIDERED: 2/6/02			
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.													

SHEET 2 OF 9

FORM PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE								ATTORNEY DOCKET NO. 1945.P3/USA/SILICON			SERIAL NO.: N/A
		LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)								APPLICANT: Shen, et al.			
										FILING DATE: Herewith			GROUP: Unknown
U.S. PATENT DOCUMENTS													
Examiner Initial		DOCKET NUMBER							DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>Alex</i>	A31	5	1	9	2	7	0	2	03/09/93	Tseng	437	47	
<i>Alex</i>	A32	5	2	0	7	8	3	6	05/19/93	Chang	134	1	
<i>Alex</i>	A33	5	2	5	6	2	4	5	10/26/93	Keller, et al.	156	643	
<i>Alex</i>	A34	5	2	8	1	3	0	2	01/25/94	Gabric, et al.	156	643	
<i>Alex</i>	A35	5	2	8	2	8	9	9	02/01/94	Balmashonov, et al.	118	723 R	
<i>Alex</i>	A36	5	3	1	2	5	1	9	05/17/94	Sakai, et al.	134	1	
<i>Alex</i>	A37	5	3	1	8	6	6	8	06/07/94	Tamaki, et al.	156	662	
<i>Alex</i>	A38	5	3	3	8	3	9	8	08/16/94	Szwejkowski, et al.	156	655	
<i>Alex</i>	A39	5	3	5	4	4	1	7	10/11/94	Cheung, et al.	156	643	
<i>Alex</i>	A40	5	3	5	6	4	7	8	10/18/94	Chen, et al.	134	1	
<i>Alex</i>	A41	5	3	5	8	6	0	1	10/25/94	Cathey	156	636	
<i>Alex</i>	A42	5	3	7	8	3	1	1	01/03/95	Nagayama, et al.	156	643	
<i>Alex</i>	A43	5	3	8	2	3	1	6	01/17/95	Hills, et al.	156	643	
<i>Alex</i>	A44	5	3	8	9	1	9	7	02/14/95	Ishimaru	156	643	
<i>Alex</i>	A45	5	4	1	3	9	5	4	05/09/95	Aydil, et al.	437	81	
<i>Alex</i>	A46	5	4	3	1	7	7	2	07/11/95	Babie, et al.	156	643.1	
<i>Alex</i>	A47	5	4	4	3	6	8	6	08/22/95	Jones, et al.	216	37	
<i>Alex</i>	A48	5	4	4	9	4	1	1	09/12/95	Fukuda, et al.	118	723 MP	
<i>Alex</i>	A49	5	5	1	4	6	2	2	05/07/96	Bornstein, et al.	437	189	
<i>Alex</i>	A50	5	5	2	1	1	1	9	05/28/96	Chen, et al.	437	187	
<i>Alex</i>	A51	5	5	2	9	1	9	7	06/25/96	Grewal	216	68	
<i>Alex</i>	A52	5	6	2	0	6	1	6	04/15/97	Keller	138	720	
<i>Alex</i>	A53	5	6	2	6	7	7	5	05/06/97	Ruberts, et al.	216	67	
<i>Alex</i>	A54	5	6	3	7	2	3	7	06/10/97	Oehrlein, et al.	216	67	
<i>Alex</i>	A55	5	6	4	4	1	5	3	07/01/97	Keller	257	324	
<i>Alex</i>	A56	5	7	5	3	5	3	3	05/19/98	Saito	437	192	
<i>Alex</i>	A57	5	7	5	6	4	0	0	05/26/98	Ye, et al.	438	710	
<i>Alex</i>	A58	5	7	6	7	0	2	1	06/16/98	Imai, et al.	438	719	
<i>Alex</i>	A59	5	7	8	8	7	7	8	08/1998	Shang, et al.	134	1	
<i>Alex</i>	A60	5	7	8	8	7	9	9	08/04/98	Steger, et al.	156	345	
EXAMINER: <i>Alex</i>										DATE CONSIDERED: 2/6/02			
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.													

SHEET 3 OF 6

FORM PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTORNEY DOCKET NO. 1945.P3/USA/SILICON				SERIAL NO.: N/A					
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)		APPLICANT: Shen, et al.											
		FILING DATE: Herewith				GROUP: Unknown							
U.S. PATENT DOCUMENTS													
Examiner Initial		DOCKET NUMBER						DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
<i>Shen</i>	A61	5	8	1	1	0	2	2	09/02/98	Savas, et al.	216	68	
<i>Shen</i>	A62	5	8	1	7	5	3	4	10/06/98	Ye, et al.	438	10	
<i>Shen</i>	A63	5	8	4	3	2	3	9	12/01/98	Shrotriya	134	1.1	
<i>Shen</i>	A64	5	8	4	9	0	9	2	12/15/98	Xi, et al.	134	1.1	
<i>Shen</i>	A65	5	8	6	6	4	8	3	02/02/99	Shiau, et al.	438	720	
<i>Shen</i>	A66	5	8	6	9	4	0	1	02/09/99	Brunemeier, et al.	438	710	
<i>Shen</i>	A67	5	8	7	4	3	6	3	02/23/99	Hoh, et al.	438	721	
<i>Shen</i>	A68	5	8	7	9	5	7	5	03/09/99	Tepman, et al.	216	68	
	A69												
	A70												
	A71												
	A72												
	A73												
	A74												
	A75												
	A76												
	A77												
	A78												
	A79												
	A80												
	A81												
	A82												
	A83												
	A84												
	A85												
	A86												
	A87												
	A88												
	A89												
	A90												
EXAMINER: <i>Shen, et al.</i>										DATE CONSIDERED: <i>2/6/02</i>			
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.													

SHEET 4 OF 6

FORM PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE									ATTORNEY DOCKET NO. 1945 P3/USA/SILICON			SERIAL NO. N/A	
		LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)									APPLICANT: Shen, et al.				
											FILING DATE: Herewith			GROUP: Unknown	
FOREIGN PATENT DOCUMENTS															
		DOCKET NUMBER							DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION		
		B1	0	2	7	2	1	4	3	06/22/88	EP Application		YES	NO	
		B2	0	3	1	4	9	9	0	05/10/89	EP Application				
		B3	0	4	6	3	3	7	5	01/02/92	EP Application				
		B4	0	5	1	6	0	4	3	12/02/92	EP Application				
		B5	0	5	5	5	5	4	6	08/18/93	EP Application				
		B6	0	6	9	7	4	6	7	02/21/96	EP Application				
		B7	0	7	4	6	0	1	5	12/04/96	EP Application				
		B8	0	7	9	0	6	3	5	02/05/97	EP Application				
		B9	4	1	3	2	5	5	9	04/08/93	German Application				
		B10	6	1	7	7	0	9	2	06/24/94	Japan			✓	
		B11	7	0	2	9	8	7	9	01/31/95	Japan			✓	
		B12	9	6	1	5	5	4	5	05/23/96	PCT			✓	
		B13	62	0	4	0	7	2	8	08/15/85	Japan Abstract				
		B14													
		B15													
		B16													
		B17													
		B18													
		B19													
		B20													
		B21													
		B22													
		B23													
		B24													
		B25													
		B26													
		B27													
		B28													
		B29													
		B30													
EXAMINER: <i>Allen Ober</i>										DATE CONSIDERED 2/6/02					
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.															

SHEET 5 OF 6

FORM PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTORNEY DOCKET NO. 1945.P3/USA/SILICON	SERIAL NO.: N/A
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT: Shen, et al.	
				FILING DATE: Herewith	GROUP: Unknown
OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)					
<i>Aydi</i>	C1	Aydi, et al., "Multiple Steady States in a Radio Frequency Chlorine Glow Discharge," <i>J. Appl. Phys.</i> , Volume 69, No. 1, January 1, 1991, pages 109-114			
<i>Hillenius</i>	C2	Hillenius, S.J., et al., "A Symmetric Submicron CMOS Technology," <i>IEEE</i> , pages 252-255, 1986			
<i>PCT</i>	C3	PCT Notification of International Search Report dated October 28, 1999			
<i>PCT</i>	C4	PCT Notification of International Search Report dated February 4, 1999			
	C5				
	C6				
	C7				
	C8				
	C9				
	C10				
	C11				
	C12				
	C13				
	C14				
	C15				
	C16				
	C17				
	C18				
	C19				
	C20				
EXAMINER		<i>Allan W. Ober</i>		DATE CONSIDERED <i>2/6/02</i>	
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.					

EXAMINER

Allan W. Ober

DATE CONSIDERED

2/6/02

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

SHEET 6 OF 6

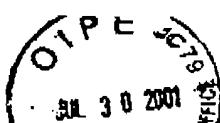
PENDING U.S. PATENT APPLICATIONS

ATTORNEY DOCKET NO.: 1945.P3/USA/SILICON
 SERIAL NUMBER: N/A
 FILING DATE: HEREWITH
 INVENTORS: SHEN, ET AL.

EXAMINER INITIAL	PENDING U.S. PATENT APPLICATIONS
D1	U.S. Patent Application entitled "Method for Improved Cleaning of Substrate Processing System"; filed July 11, 1997; Serial No. 08/893,922; Inventors: Kao, et al. = 6,125,857
D2	U.S. Patent Application entitled "Apparatus for Improved Remote Microwave Plasma source for Use with Substrate Processing Systems"; filed April 23, 1997; Serial No. 08/839,111; Inventors: Kao, et al. = 6,026,762
D3	U.S. Patent Application entitled "Method and Apparatus for Determining the Endpoint in a Plasma Cleaning Process"; filed July 2, 1997; Serial No. 08/887,165; Inventors: Subrahmanyam, et al. = 6,071,424
D4	U.S. Patent Application entitled "Apparatus and Method for Efficient and Compact Remote Microwave Plasma Generation"; filed April 22, 1997; Serial No. 08/839,007; Inventor: Bhatnagar = 6,049,622
D5	U.S. Patent Application entitled "Method and Apparatus for Pre-stabilized Plasma Generation for Microwave Cleaning Applications"; filed November 13, 1996; Serial No. 08/746,650; Inventors: Fong, et al. = 5,939,831
D6	U.S. Patent Application entitled "Inductively Coupled HDP-CVD Reactor"; filed May 29, 1997; Serial No. 08/865,018; Inventors: Redeker, et al. = 6,182,602
D7	U.S. Patent Application entitled "Symmetric Tunable Inductively Coupled HDP-CVD Reactor"; filed July 13, 1996; Serial No. 08/679,927; Inventors: Redeker, et al. = 6,170,428
D8	U.S. Patent Application entitled "Apparatus and Methods for Upgraded Substrate Processing System with Microwave Plasma Source"; filed March 5, 1997; Serial No. 08/811,627; Inventors: Tanaka, et al. = 6,039,831
D9	U.S. Patent Application entitled "Microwave Apparatus for In-situ Vacuum Line Cleaning for Substrate Processing Equipment"; filed October 30, 1996; Serial No. 08/741,241; Inventors: Fong, et al. = 6,045,618
D10	
D11	
D12	
D13	
D14	

SHEET 1 OF 1

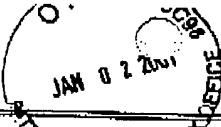
U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)		ATTORNEY DOCKET NO. 1945.P3/SILICON/CLEANGAS			SERIAL NO.: 09/507,629							
		APPLICANT: SHEN, ET AL.			FILING DATE: 2/18/00							
U.S. PATENT DOCUMENTS												
Examiner Initial	DOCKET NUMBER			DATE	NAME	CLASS						
XW	AA	4	7	3	8	7	4	8	04/19/88	KISA	156	643
XW	AB	4	7	7	9	9	9	9	11	DOCKREY	438	719
	AC											
	AD											
	AE											
	AF											
	AG											
	AH											
	AI											
	AJ											
	AK											
FOREIGN PATENT DOCUMENTS												
	DOCKET NUMBER			DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION				
								YES	NO			
	AL											
	AM											
	AN											
	AO											
	AP											
OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)												
	AQ											
	AR											
	AS											
	AT											
	AU											
	AV											
	AW											
	AX											
EXAMINER	<i>M. - O.</i>						DATE CONSIDERED 2/6/02					
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.												



SHEET 1 OF 1

FORM PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT & TRADEMARK AND TRADEMARK OFFICE		ATTORNEY DOCKET NO. 001945 USA P03/ETCH/ SILICON/JB		SERIAL NO 09/507,629						
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)		APPLICANT: Shen, et al.										
		FILING DATE: 02/18/2000		GROUP: 1746								
U.S. PATENT DOCUMENTS												
Examiner Initial		DOCKET NUMBER				DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE		
<i>AAC</i>	AA	5	7	4	1	3	9	6	04/21/98	Loewenstein	152	643,1
<i>AAC</i>	AB	5	6	5	1	8	8	6	07/29/97	Keller, et al	152	643,1
<i>AAC</i>	AC											
<i>AAC</i>	AD											
<i>AAC</i>	AE											
<i>AAC</i>	AF											
<i>AAC</i>	AG											
<i>AAC</i>	AH											
<i>AAC</i>	AI											
FOREIGN PATENT DOCUMENTS												
		DOCKET NUMBER				DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION		
<i>AAC</i>	AJ	0	8	3	7	4	9	7	04/22/98	EP	YES	NO
<i>AAC</i>	AK	0	2	0	0	9	5	1	04/11/00	EP	YES	NO
<i>AAC</i>	AL										YES	NO
<i>AAC</i>	AM										YES	NO
<i>AAC</i>	AN										YES	NO
OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)												
<i>AAC</i>	AO	PCT Report dated 06/22/01, European Patent Office, P.B. 5818 Patentlaan 2 NL-2280 HV Rijswijk										
<i>AAC</i>	AP	Zaleski, et al "Tungsten Silicide/Polysilicon Stack Etching using Mixed Fluorine Chlorine Chemistry in a High Density Plasma Chamber", Electrochemical Society Proceedings Volume 98-4, pages 203-209.										
<i>AAC</i>	AQ	<i>AAC - Ora</i>										
EXAMINER								DATE CONSIDERED				
								2/6/02				
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.												

SHEET 1 OF 1



FORM PTO-1449 U. S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTORNEY DOCKET NO. 1945 P3/USA/SILICON						SERIAL NO. 09/507,609				
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)		APPLICANT: Shen, et al.										
		FILING DATE: 02/18/2000						GROUP: 1746				
U. S. PATENT DOCUMENTS												
Examiner Initial		DOCKET NUMBER					DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)	
<i>AAC</i>	AA	5	7	00	00	7	4	Liao	438	713		
<i>AAC</i>	AB	66	00	99	00	77	11	Hajime, et al.	438	714		
	AC										<i>RECEIVED</i>	
	AD											
	AE											
	AF										<i>GROU 700</i>	
	AG											
	AH											
	AI											
FOREIGN PATENT DOCUMENTS												
		DOCKET NUMBER					DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
<i>AAC</i>	AJ	0	1	0	5	0	4	Japan			YES	NO
<i>AAC</i>	AK	1	0	2	3	3	8	Japan				
<i>AAC</i>	AL	0	7	0	9	8	7	EP			x	
	AM											
	AN											
OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)												
<i>AAC</i>	AO	PCT Search Report dated 11/8/00.										
	AP											
	AQ											
EXAMINER <i>AAC - Oba</i>		DATE CONSIDERED 2/8/02										
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.												

JAN 17 2007
U.S. PATENT AND TRADEMARK OFFICE

X-7

SHEET 1 OF 1

FORM PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		DOCKET NO. 001945 USA POMETCH/SILICON/JB				APPLICATION NO: 09/507,629			
INFORMATION DISCLOSURE STATEMENT IN AN APPLICATION (Use several sheets if necessary)		APPLICANT: Sher, et al.									
		FILING DATE: 2/18/2000				GROUP ART UNIT: Unknown					
U.S. PATENT DOCUMENTS											
EXAMINER INITIAL	DOCUMENT NUMBER						DATE	NAME	CLASS	SUBCLAS S	FILING DATE IF APPROPRIATE
<i>Amo</i>	5	2	1	9	4	8	5	06/15/93	Wang, et al.	252	079,3
<i>Amo</i>	5	2	5	9	9	2	3	11/09/93	Hori, et al.	156	643
<i>Amo</i>	5	3	5	4	4	1	6	10/11/94	Okudaira, et al.	156	643
										<i>RECEIVED FEB - 4 2002 TC 1700</i>	
FOREIGN PATENT DOCUMENTS											
	DOCUMENT NUMBER				DATE	COUNTRY	CLASS	SUBCLAS S	TRANSLATION		
									YES	NO	
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)											
EXAMINER	<i>Alex. Ota</i>									DATE CONSIDERED <i>3/27/02</i>	
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.											



SHEET 1 OF 1

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP
conformance and not considered. Include copy of this form with next communication to applicant.

C:\CLIENT\APPLIED\Chamber Cleaning\1945.PS\PTO-1469.DOC7.wpd

JAN 3 0 2003

SHEET 1

FORM PTO-1440 TRADEMARKS DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		DOCKET: 001945 USA P03/ETCH/SILICON/SB		APPLICATION NO: 09/507,629	
INFORMATION DISCLOSURE STATEMENT IN AN APPLICATION (Use several sheets if necessary)		APPLICANT: SHEN et al.			
		FILING DATE: 02/18/2000		GROUP ART UNIT: 1240 1763	
U.S. PATENT DOCUMENTS					
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS
<i>JKO</i>	5,259,923	11/9/1993	HORT et al.		DUPPLICATE
<i>JKO</i>	5,384,009	1/24/1995	MAK et al.		
<i>JKO</i>	5,180,464	1/19/1993	TATSUMI et al.		
<i>JKO</i>	6,270,634	8/7/2001	KUMAR et al.		
<i>JKO</i>	6,125,859	10/3/2000	KAO et al.		RECEIVED
<i>JKO</i>	5,861,233	1/19/1999	SEKINE et al.		JAN 9 2002 IC 1700
FOREIGN PATENT DOCUMENTS					
DOCUMENT NUMBER	DATE	COUNTRY	CLASS	ABSTRACT	
				YES	NO
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)					
<i>JKO</i>	Kimizuka, Masakatsu et al. "Pattern Profile Control in Magnetron reactive ion etching of Poly-Si." J. Vac. Sci. Technol. B 10(5), Sept/Oct 1992. pp. 2192-2196.				
EXAMINER:		DATE CONSIDERED: <i>5/24/03</i>			
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.					